

Form PTO-1449		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE			ATTY. DOCKET NO. M122-1904		PRIORITY SERIAL NO. 08043,116	
LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)					APPLICANT Michael Nuttall et al.		10/050426	
					PRIORITY FILING DATE 1/15/02 April 24, 2001		PRIORITY GROUP 2813	
U.S. PATENT DOCUMENTS								
*Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate		
~	AA	4,497,683	02/1985	Celler et al.	156	603		
~	AB	4,963,506	10/1990	Liaw et al.	438	482		
~	AC	5,080,933	01/1992	Gruppen-Semansky et al.	427	255.1		
~	AD	5,110,757	05/1992	Arst et al.	438	489		
~	AE	5,124,276	06/1992	Somara et al.	438	607		
~	AF	5,364,815	11/1994	Osada	438	489		
~	AG	5,441,012	08/1995	Aketagawa et al.	117	86		
~	AH	5,006,911	04/1991	Sivan	357	23.11		
~	AI	5,818,100	10/1998	Grider et al.	257	616		
~	AJ	5,037,775	08/1991	Reisman	437	89		
~	AK	5,646,073	07/1997	Grider et al.	437	233		
FOREIGN PATENT DOCUMENTS								
	Document Number	Date	Country	Class	Subclass	Translation		
						Yes	No	
	AL							
	AM							
	AN							
	AO							
	AP							
OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)								
~	AR	Violette, Kathy, et al., "Low Temperature Selective Silicon Epitaxy by Ultra High Vacuum Rapid Thermal Chemical Vapor Deposition Using Si <sub>3</sub> H <sub>8</sub> , H <sub>2</sub> , and Cl <sub>2</sub> ", Appl. Phys. Lett., Vol. 68(1), pp. 66-68 (January 1996).						
~	AS	Wolf, Stanley, et al., "Chemical Vapor Deposition of Amorphous and Polycrystalline Films, Silicon Processing for the VLSI Era", Vol. 1: Process Technology, pp. 183 and 191 (Lattice Press).						
	AT							
EXAMINER: <i>Samuel</i>				DATE CONSIDERED: 8/1/02				
*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.								

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U.S. PATENT DOCUMENTS							
*Examiner Initial	Document Number	Date	Name	Class	Subclass	Fr. Date Appropriate	
~	AA	6,013,575	01/2000	Itoh	438	61	
~	AB	4,948,755	08/1990	Mo	437	195	
~	AC	4,966,868	10/1990	Murali et al.	437	193	
~	AD	5,607,878	03/1997	Otsuka et al.	437	187	
~	AE	5,663,098	09/1997	Creighton et al.	438	675	
~	AF	6,017,823	01/2000	Shushiguchi et al.	438	696	
~	AG	6,069,036	05/2000	Kim	438	238	
~	AH	5,798,278	08/1998	Chan et al.	437	43	
~	AI	5,037,779	08/06/91	Reisman	437	89	
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FOREIGN PATENT DOCUMENTS							
	Document Number	Date	Country	Class	Subclass	Translation	
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	AT						
EXAMINER <i>[Signature]</i>				DATE CONSIDERED <i>8/1/04</i>			
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